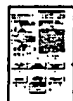




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JP63225602A2: EASILY SOLUBLE CHITOSAN

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Country: **JP Japan**

Kind:

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Issued/Filed Dates: **Sept. 20, 1988 / March 13, 1987**

Application Number: **JP1987000059229**

IPC Class: **C08B 37/08;**

Abstract:

Purpose: To form an easily soluble chitosan which dose not need a large amount of an acid or water when used, is nearly odorless, can be stored for a long term and can be used at a high concentration, by dehydrating an aqueous solution of chitosan salt which is a reaction product of chitosan and an acid, followed by powdering.
Constitution: This easily soluble chitosan is formed by dehydrating an aqueous solution of a chitosan salt which is a reaction product of chitosan and an acid, followed by powdering. As chitosan, one which is conventionally employed can be used as it is. As an acid which will be reacted with chitosan, either a mineral acid or an organic acid may be used, hydrochloric acid can be mentioned as the mineral acid, and acetic acid, lactic acid, citric acid, succinic acid, etc. as the organic acid. The reaction of chitosan with the acid is carried out generally in the presence of water in order to conduct the reaction smoothly. As a method of the dehydration and powdering, a usual method for producing a powder can be employed (e.g., spray drying, drum drying, freeze-drying, etc.).
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Other Abstract Info: **DERABS C88-304874 DERC88-304874**

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